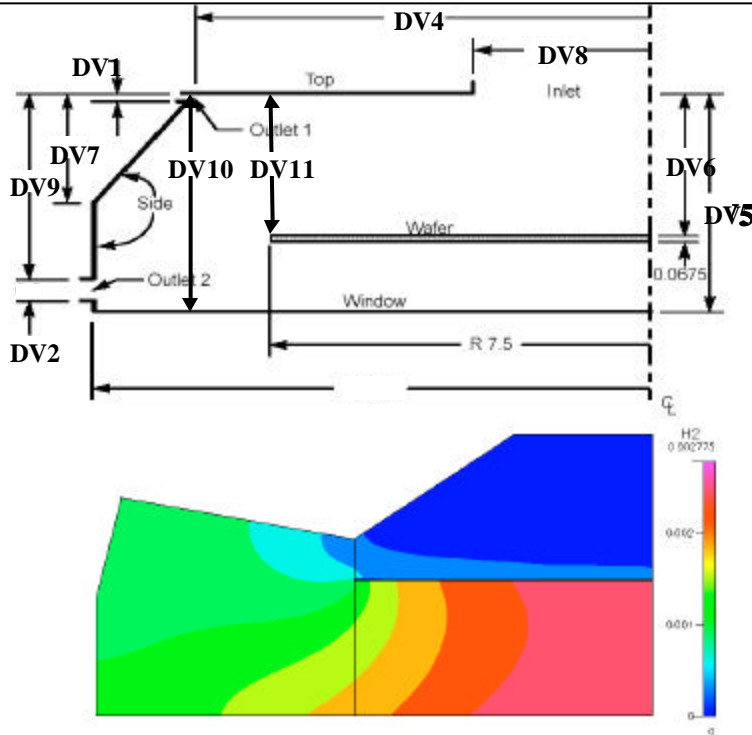


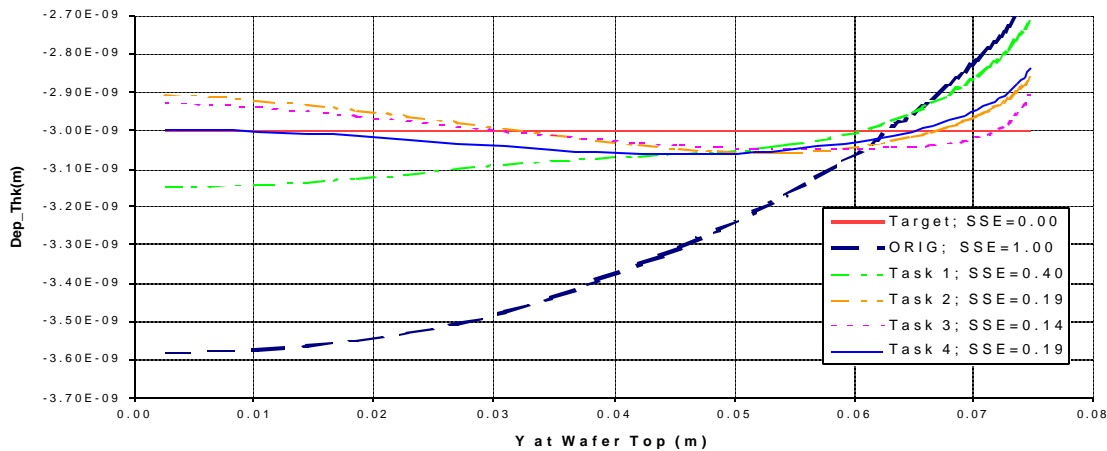
# VisualDOC/CFDRC Geometry Optimization of a Chemical Vapor Deposition Reactor



VisualDOC and CFDRC Software is used to search for an optimal reactor configuration whose chemical vapor deposition layer is as uniform as possible along the wafer surface, and as close to a prescribed thickness as possible.

Optimized Configuration H2 Mass Fraction Contours

### Si Deposition onto Wafer



VisualDOC is used to optimize the reactor geometry in order to achieve thinner uniform deposition layers with respect to a prescribed target thickness.

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